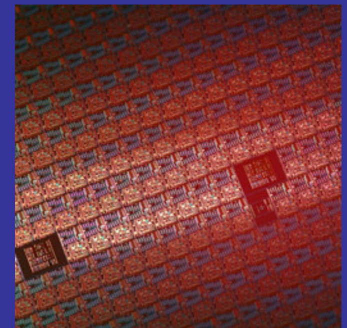
Accelerating the next technology revolution

IEUVI Optics Contamination / Lifetime TWG Meeting

October 2, 2008 – Lake Tahoe, CA, US

Chair: A. Wüest, SEMATECH
Co-chairs:
Asia/Pacific: Y. Fukuda, Canon
Europe: R. Verberk, TNO
US: T. Lucatorto, NIST
K. Orvek, Intel/SEMATECH



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International EUV Initiative (IEUVI)

IEUVI
International EUV Initiative

Europe

- MEDEA+, CATRENE
- ENIAC, AENEAS
- LETI
- IMEC

United States

- SEMATECH
- INVENT, CNSE
- SRC

Asia / Pacific

- ASET
- EUVA
- SELETE

IEUVI Mission: To further the coordination of collaborative efforts among leading EUVL R&D consortia.

http://www.ieuvi.org

IEUVI Organization

IEUVI Board

Chair:	Paolo Gargini	Intel		
Member Organizations:	CEA / LETI	(EU)	Selete	(JP)
	IMEC	(EU)	EUVA	(JP)
	MEDEA+, CATRENE, ENIAC, AENEAS	(EU)	SEMATECH	(US)

IEUVI Technical Working Groups (TWG)

Optics Contamination TWG

Chair:	Andrea Wüest	(US)	SEMATECH
Co-Chairs:	Yasuaki Fukuda	(JP)	EUVA / Canon
	Rogier Verberk	(EU)	TNO
	Tom Lucatorto	(US)	NIST

Resist TWG

Chair:	Serge Tedesco	(EU)	CEA / LETI
Co-Chair	Jacque Georger	(US)	SEMATECH / Intel
	TBD	(AP)	

Mask TWG

Chair:	Kevin Orvek	(US)	SEMATECH / Intel
Co-Chairs:	Iwao Nishiyama	(JP)	Selete / NECEL
	Jinho Ahn	(KR)	Hanyang Univ.
	Jan Hendrik Peters	(EU)	AMTC

Source TWG

Chair:	Frank Goodwin	(US)	SEMATECH
Co-Chair:	Masashi Ogawa	(JP)	EUVA
	TBD	(EU)	

Agenda

Lake Tahoe, CA, USA - October 2, 2008

7:45`	Breakfast	
8:00	Welcome and Introductions	A. Wüest, SEMATECH
8:15	Survey Results	A. Wüest, SEMATECH
	Exposure Tool Update on Contamination Issues	
8:30	• SFET Optics Contamination Learning Update	Iwao Nishiyama, Selete
8:45	• Intel MET Cold Trap results and Related Data	Roman Caudillo, Intel
9:00	• NIST Tools to Characterize Resist Outgas and Analyze Stepper Contaminants	Thomas Lucatorto, NIST
9:15	• Contamination and Cleaning of MET Illumination Mirrors	Erik Sohmen, Carl Zeiss SMT
9:30	• EUV Mask Contamination During Use	Ted Liang, Intel
9:45	• Discussion	
10:00	Break	
	Resist Outgassing Contribution	
10:20	• Collector Upgrade for Higher Power Optics Contamination Testing	Gregory Denbeaux, CNSE
10:35	• EUV Resist Outgassing Activity at Selete	Toshiro Itani, Selete
10:50	• SEMATECH Policy on EUV Resist Outgassing	Kevin Orvek, Intel/SEMATECH
11:05	• Photoresist Outgassing for EUV HVM Exposure Tool by Canon and Nikon	Takashi Aoki, Nikon
11:20	• Resist Outgas Metrology Update	Noreen Harned, ASML
11:35	• Discussion	
12:00	Adjourn	

Next IEUVI Optics Contamination and Lifetime TWG Meeting

- SPIE Advanced Lithography, San Jose, CA, USA
- February 26, 2009
- Presentations will be available on www.ieuvi.org

Thank you

Thank you very much for your participation and contribution!